

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
S1	22	"205"/\$.ccls. and "204"/\$.ccls. and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5 plating) and ((tilt\$3 inclin\$3) near10 (substrate workpiece wafer)) and ((parallel) near15 anode)	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 14:21
S2	2	"205"/\$.ccls. and "204"/\$.ccls. and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5 plating) and ((tilt\$3 inclin\$3) near10 (substrate workpiece wafer)) and ((parallel) near15 anode) and oscillat\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:03
S3	13	"205"/\$.ccls. and "204"/\$.ccls. and (electrolysis electrolytic electrochemic\$4 electrodeposit\$5 electroplat\$5 plating) and ((tilt\$3 inclin\$3) near10 (substrate workpiece wafer)) and oscillat\$3	US-PGPUB; USPAT; USOCR; EPO; JPO; DERWENT; IBM_TDB	OR	ON	2005/11/17 15:04